

		Subclass		PATENT NUMBER
		Class	ISSUE CLASSIFICATION	
				

**U.S. UTILITY Patent Application**

<i>M H G</i>	O.I.P.E.	PATENT DATE <i>2011</i>
SCANNED	G.A.	

APPLICATION NO. 09/901038	CONT/PRIOR F	CLASS 438 156	SUBCLASS 70	ART UNIT 1765	EXAMINER <u>Crowell</u> <u>Heath DEO</u>
APPLICANTS		Toshihiro Yamashita Hirotoshi Ise <u>345.28</u>			
TITLE Plasma Processing system in which wafer is retained by electrostatic chuck, plasma processing method and method of manufacturing semiconductor device					

## **ISSUING CLASSIFICATION**

<input type="checkbox"/> <b>TERMINAL DISCLAIMER</b>		<b>DRAWINGS</b>			<b>CLAIMS ALLOWED</b>	
		<b>Sheets Drwg.</b>	<b>Figs. Drwg.</b>	<b>Print Fig.</b>	<b>Total Claims</b>	<b>Print Claim for O.G.</b>
<input type="checkbox"/> The term of this patent subsequent to _____ (date) has been disclaimed.					<b>NOTICE OF ALLOWANCE MAILED</b>	
<input type="checkbox"/> The term of this patent shall not extend beyond the expiration date of U.S Patent No. _____  _____  _____		(Assistant Examiner) _____  (Primary Examiner) _____			(Date) _____	
<input type="checkbox"/> The terminal _____ months of this patent have been disclaimed.					<b>ISSUE FEE</b>	
					<b>Amount Due</b>	<b>Date Paid</b>
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